

## Reliability Effects with Proofing of Tantalum Capacitors

Bill Long<sup>1</sup>, Mike Prevallet<sup>2</sup>, John D. Prymak<sup>3</sup>

KEMET Electronics Corp.

1515 E. Woodfield Rd., Suite #350, Schaumburg, IL. 60173<sup>1</sup> / PO Box 5928, Greenville, SC 29606<sup>2,3</sup>

847-517-1030<sup>1</sup> / 864-963-6300<sup>2,3</sup> (Phone)

847-517-1037<sup>1</sup> / 864-967-6876<sup>2,3</sup> (FAX)

[billlong@kemet.com](mailto:billlong@kemet.com)<sup>1</sup> / [mikeprevallet@kemet.com](mailto:mikeprevallet@kemet.com)<sup>2</sup> / [johnprymak@kemet.com](mailto:johnprymak@kemet.com)<sup>3</sup> (Email)

### Abstract

In traditional tantalum capacitors, the construction consists of a tantalum anode,  $Ta_2O_5$  dielectric, and  $MnO_2$  as the cathode. The benefit of having  $MnO_2$  as the cathode, is the self-healing effect it provides. The conversion of  $MnO_2$  to a higher resistive state allows fault sites within the dielectric to be shut off from the rest of the capacitor. To mitigate problems developed during reflow, it is recommended for tantalum capacitors to be derated 50% for power-on reliability. Many times, customers are forced to use tantalum capacitors outside the recommended ranges. To improve power-on reliability, we recommend proofing the capacitors. Proofing, or controlled power up, is the process of activating the self-healing effects of tantalum capacitors. Although it has been shown to improve power-on performance and in some instances eliminate problems, the measurable effects of proofing have not been reported. This paper will investigate the measurable effects of proofing.

### Why is proofing required

The tantalum capacitor is typically built with three to four times the dielectric thickness required for its rated voltage. It is tested and exposed to voltages that are at least 132% of rated voltage, and it is usually used at applications voltages less than its rated. Then how is it that the dielectric can break down suddenly at voltages well below its rating?

The changes take place during the solder attachment process. This device is 100% electrically tested and put into pick-and-place feeder reels. In this position, the device still maintains the dielectric quality and capability verified through the electrical inspection. The pieces are removed from the reels, placed on the circuit boards, and then soldered, usually by reflow solder techniques. It is in this procedure that the device can change. Looking at the structure of the surface-mount tantalum capacitors reveals a metal pellet structure (tantalum, tantalum pentoxide, and manganese dioxide) surrounded by the plastic molding compound (Figure 1). The pellet is attached to the anode portion of the leadframe through a conductive epoxy that bonds two faces of the pellet to the metal leadframe. The cathode riser wire at the other end of the pellet is welded to the leadframe at the oppo-

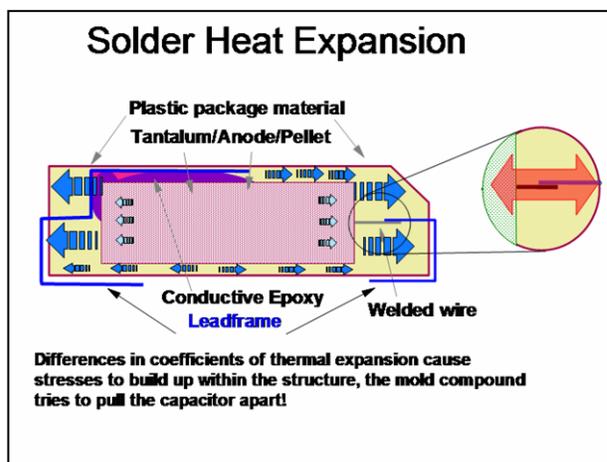


Figure 1. Mismatch of CTEs in tantalum solid-state capacitor.<sup>[1]</sup>

site side to create the anode extension out of the plastic package.

During the solder operation, the entire package passes through the solder temperatures, causing the elements to expand at different rates according to each element's coefficient of thermal expansion (CTE). The plastic expands at a much greater rate than the metallic elements and this creates mechanical tensile forces on the pellet structure. This mismatch is made much worse once the temperature rises above the glass transition temperature of the plastic (approximately 180°C), close to doubling the rate of expansion for the duration that the device is held above this temperature. The longer the device resides at this temperature above the glass transition, the greater the magnitude of forces that the pellet must experience.

Looking at the structure in this state, the possible defects that might be created here are centered on the weld of the riser wire to the leadframe (anode) and the epoxy attachment of the pellet to the leadframe (cathode). Disruptions of these contacts could lead to high DF or ESR parameters in the capacitor, or an intermittent to open capacitance.<sup>[1]</sup>

Once the device passes through the peak temperature of the reflow, the heat diminishes and the elements now begin to shrink, as they cool down. It is this aspect of the solder profile that we believe the damage is created to the dielectric that could lead to dielectric breakdowns.

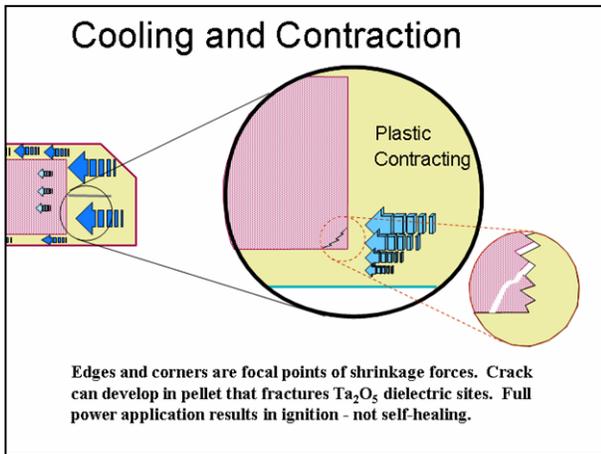


Figure 2. Contraction and compressive forces.

As depicted in Figure 2, the elements might not fit back together as perfectly as they once were before the heat generated expansion. Huge compressive forces could be placed on the pellet structure. Along the edges and corners, these forces could create a fracture in a very small portion of the pellet structure – if the pellet structure is fractured, there is a place in the dielectric where the dielectric is fractured.

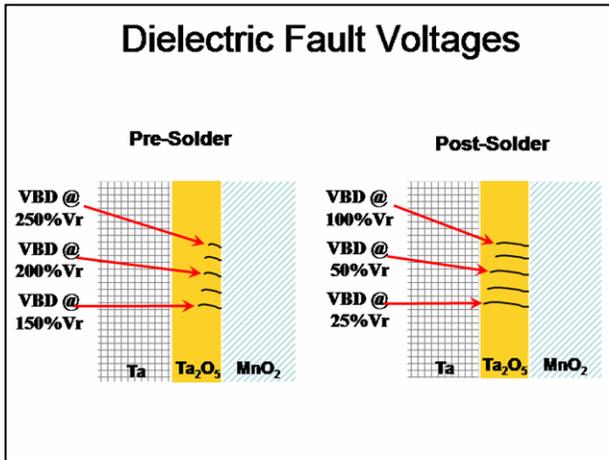


Figure 3. Fault expansion after solder process/

Even without the pellet fracturing, there may be enough compressive force on the pellet to allow a fault site in the dielectric that was not susceptible to voltages already experienced (132% of rated voltage), to grow or extend further into the dielectric to now become a breakdown site at voltages well below the rated voltage. The change in breakdown levels for the dielectric can be viewed in Figure 3. On the left are a series of faults as they might appear after 100% electrical testing and the pieces are placed in the reels. Though the faults exist, they are sensitive to voltages well above those of the rated voltage. The diagram on the right might represent a post-solder condition where these faults have expanded further into the dielectric and now are sensitive to voltages at or below the rated voltage.

Though not shown, there are faults that exist in the pre-solder devices that are healed, whereby the  $MnO_2$  has been converted locally at the point of contact with this material to  $Mn_2O_3$ . This converted material has much higher resistivity and effectively pinches off the fault current into these points – eliminating them from the active capacitor circuit.

### Proofing procedure

The devices tested were all similar devices (T491D226M035), from three different production batches. The samples were mounted on FR4 test cards using reflow profiles with peak temperatures around 232°C. Each test card held 20 pieces each, with a common terminal (anode) connected to one edge pin, and the 20 cathodes to individual pins along the card edge. “Proofing” involved the application of a selected DC voltage to each capacitor through a 1-kOhm resistor. After 7 seconds application, the voltage across the capacitor was verified to be within 99% of the applied voltage. If the voltage was less than this level, the capacitor was charged for another 7 seconds and the level was again verified to be within 99% of the applied voltage.

A control group was created to see the effects of “no proofing,” and four additional groups of “proofed” capacitors at rated voltage, rated voltage plus 1 VDC, rated voltage plus 2 VDC, and rated voltage plus 4 VDC, were created.

### I. Scintillation Test Results

Scintillation testing consists of the application of a small constant current to each capacitor and monitoring the voltage rise versus time.<sup>[2]</sup> The theory is that the voltage will continue to rise until the voltage reaches a predetermined compliance level or until the weakest dielectric point is achieved (the scintillation or breakdown voltage for that piece). Secondary scintillations may be at different points within the dielectric (should always be at higher level than any previous), but may also be secondary cracks or fault sites created by the energy burst of the initial scintillation (allowing secondary to be of lower magnitude than any previous). The scintillation voltages from a group of pieces then represent a cumulative indication of the dielectric quality (fault distribution) for that group.

In Figure 4, a scintillation test for one of the pieces is captured. The constant current was selected to be 150 uA, and there is an initial  $dv/dt$  that rises up to 79.44 VDC, and then collapses down below 5 VDC. The difference in energy levels represents a change in energy of 70.43 mJoules.

We also use the  $dv/dt$  of the 1<sup>st</sup> eight points to estimate the capacitance (assuming no leakage current at these very low voltages), shown here as 22.755 uF. Once we establish the capacitance, we then assume that

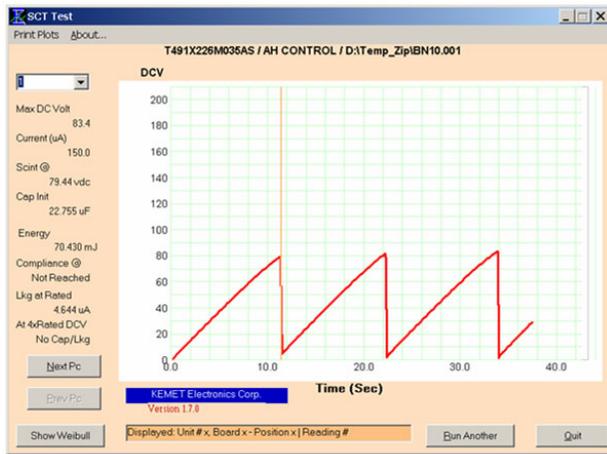


Figure 4. Scintillation event for single piece.

a change in the  $dv/dt$  slope for the 5 points nearest the rated voltage are due to the loss of charging current as leakage current, and an estimate of the leakage current is shown to be 4.644  $\mu A$ . The scintillation voltage ranking for each piece represents the first scintillation voltage level, or as in the case of this piece at 79.44 VDC.

Figure 5 represents the collective scintillation voltages for a single group of 98 pieces, with the cumulative percentage plotted against the scintillation voltage level (Breakdown voltage). A linear fit is established for the lower voltages through 47 of the 98 points. The points selected are those that give the best correlation coefficient (RR). Projecting the linear fit allows a projection of the voltages required to achieve 1, 10, and 100-PPM failure rates although the confidence bands (not shown) get wider as the linear fit moves away from the data population.

The results of this testing on the 5 groups of capacitors results in the 100 PPM failure rate (FR) voltage levels as depicted in Figure 6. The three batches are identified as BN10, HJ40, and HK40. The leftmost bar in each batch represents the control group, or pieces that were mounted and tested, with no proofing. In order

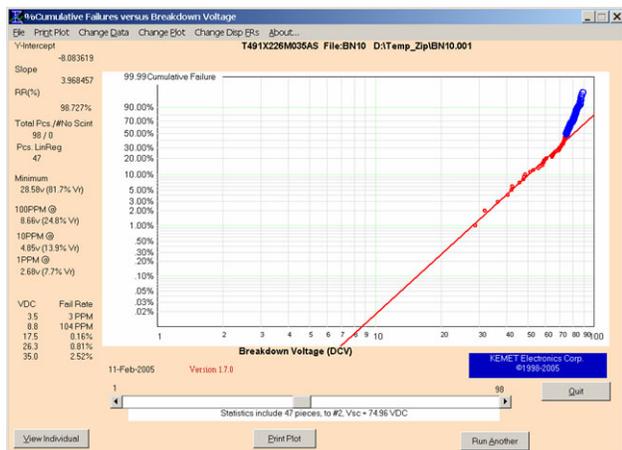


Figure 5. Weibull plot of data with linear fit.

from left to right in each batch, are the groups proofed at rated voltage ( $V_R$ ),  $V_R+1$  VDC,  $V_R+2$  VDC, and  $V_R+4$  VDC.

The BN10 and HK40 groups show a large variation between the control groups and the proofed groups, whereas the HJ40 batch does not show this variation. One would think that as the proof voltage is increased, there would be a direct correlation between that magnitude and the 100-PPM failure rate levels, but this is not the case. These voltages are not that much different, and the 100-PPM extrapolation does have a reduced level of confidence.

### 100-PPM Failure Rate Voltage Level T491X226M035

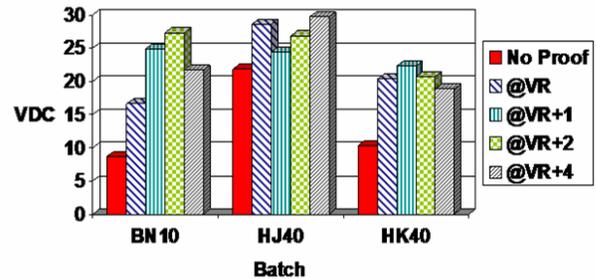


Figure 6. Scintillation projection of 100-PPM FR voltages.

Looking at a failure rate of voltage level within the grouping would allow a tighter confidence. In Figure 7, the failure rate at the recommended application voltage of  $\frac{1}{2}$  of  $V_R$ , reveals a much more extreme separation between the control (no proofing) and all the proofed groups for two batches. It is also apparent that batch HJ40 was not affected as much as the other two groups. This brings up one of the reasons why some batches appear to cause problems, and others do not. Proofing HJ40 had no significant impact on the failure rate at 50%  $V_R$ , whereas there were large impacts on batches BN10 and HK40.

### Failure Rate @ 50% Voltage Rating T491X226M035

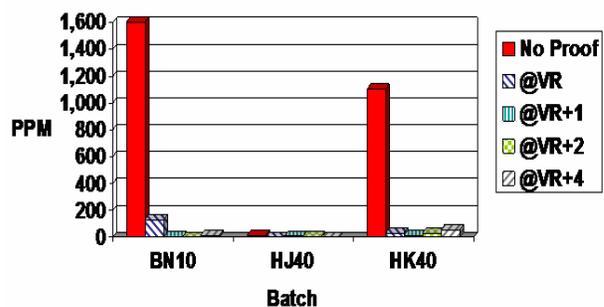


Figure 7. Scintillation projected FRs at 50%  $V_R$ .

## II SSST Test Results

In a nearly opposite approach to scintillation testing, SSST (Step Stress Surge Test<sup>[3]</sup>) evaluations use as large of a current as possible to drive the voltage across the capacitor to a predetermined level, as quickly as possible. A high power, high current is supplemented with a large bank of capacitors across the output of the supply to allow as quick a transfer of energy as possible. The energy is switched through three parallel FETs, each with an  $R_{DS(ON)}$  resistance of 10 milliohms.

The voltage normally starts at 50% of  $V_R$ , and is incremented after the capacitor withstands four ON pulses and four OFF pulses (duration is ½ second ON and ½ second OFF) applied sequentially. In a 10-millisecond window before the pulse is transitions to OFF, the voltage across the test capacitor is measured and must be within 90% of the applied voltage to be considered successful. Falling below this level indicates a failure. The purpose of this test is to mimic a power-on condition of unimpeded current, and to drive the fault to a catastrophic failure.

In the same manner as scintillation, the breakdown voltages for a group of pieces are analyzed to create a linear fit and allow an extrapolation of the low PPM failure levels. As with the scintillation test, the center group, HJ40, appears to be little effected by the proofing, as the difference from control to the proofed groups seems minor.

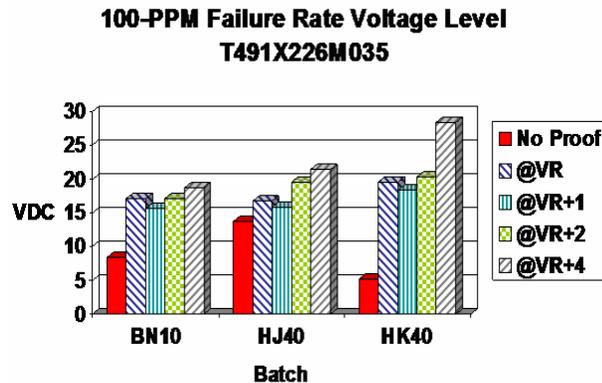


Figure 8. SSST projections of 100-PPM FR voltages.

In the same manner as the scintillation data, the differences of the different proofing voltages appear inconsistent. Again, because of the wider confidence spread for this extrapolated level (100-PPM), using a level closer to the distribution of the data points will reduce the uncertainty. Looking at that data as the failure rate at 50% of  $V_R$  as in Figure 9, the plot is very close to that of the scintillation test of Figure 7.

## Failure Rate @ 50% Rated Voltage T491X226M035

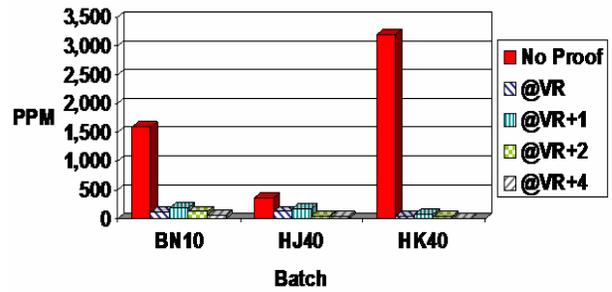


Figure 9. SSST derived failure rates at 50%  $V_R$ .

The control group (No Proof) of batch HJ40 shows very low failure rates at the 50%  $V_R$  level – equal to those achieved with the other two batches, BN10 and HK40, only after proofing. This reinforces the concept that there is difference in these batches after the solder process, with batches BN10 and HK40 being weaker.

## III Life Test

The results in this test are not supportive of the other testing, but we made a terrible mistake in setting this test up. We wanted to create failures in these groups that were in the order of percentages, so we ran the test at 125°C with rated voltage. After all, we proofed them at rated voltage, so we thought we were not introducing any additional stress. The fact is that the rated voltage for this tantalum capacitor drops to 67% of the nameplate voltage at 125°C. When we set up the test to run these at rated voltage at 125°C, we actually were applying 150% of the rated voltage at this temperature.

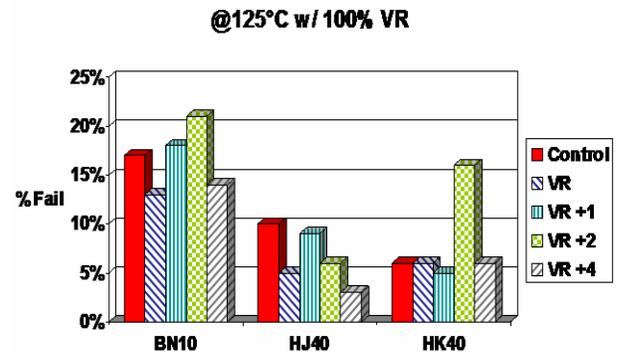


Figure 10. Life test results.

There is no pattern, no rhyme or reason. By over-stressing well above the proofing strain, we incurred the desired percentage failures, but obscured the effects of the proofing.

## **Conclusions**

The effects of the proofing are in line with the supposition that clearing the dielectric of these fault sites enhances reliability of the component, but most significantly in weaker components. Variations from batch to batch could present groups where this procedure has little effect, but it will have effect on the weaker batches to bring them up to the capability of the stronger batches. Variations in solder may create these same good/bad variations.

The life test should have been run at 85°C and at the same strain level as the minimum proofing voltage. Sample size should be increased to assure that variations below 1% are detectable.

Testing should also be run at voltages below the rated. In most cases, our customers are using the part near 50% of rated voltage, and the elimination of these power-on failures does not need the proofing voltage to be at the rated voltage of the part. A slight increase over

the maximum projected voltage exposure should be duplicated in future test as well.

We have been successful in relating our customers' successes created by instituting a proofing method in their process to a measurable effect in improved reliability.

## **Bibliography**

- [1.] Prymak, J.; "*Power-on Failures in Tantalum and Aluminum SMT Capacitors*"; CARTS 2002; Components Technology Institute, Inc.; March, 2002
- [2.] Prymak, J.; "*Update – Scintillation Testing in Tantalum Capacitors*"; unpublished; KEMET Electronics Corp.; January, 2000
- [3.] Marshall, J. and Prymak, J.; "*Surge Step Stress Testing (SSST) of Tantalum Capacitors*"; CARTS 2001; Components Technology Institute, Inc.; March, 2001